FILING DATE February 11, 2002 GROUP

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U.S. PATENT DOCUMENTS										
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EXAMINER INITIAL										
1		Todd, Michael A. et al., "Deposition of Si <sub>1-x</sub> Ge <sub>x</sub> Films for Gate Electrode Applications Using a Novel Approach," ICSI3, The SiGe Conference; Santa Fe, NM, March 2003								

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(USE SEVERAL SHEETS IF NECESSARY)

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. ASMEX.387A

APPLICATION NO. 10/074,534

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

APPLICANT

APPLICANT Michael A. Todd

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FILING DATE
February 11, 2002

GROUP 2814

					U.S. PATENT DOCUMENTS	-		
	MINER TIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
1	V	1.	5,389,398	02/14/95	Suzuki et al.	427	130	
7		2.	5,698,771	12/16/97	Shields et al.	73	31.05	
		3.	6,228,181	05/08/01	Yamamoto et al.	148	33.5	
		4.	6,326,311	12/04/01	Ueda et al.	438	694	
		5.	6,455,892	09/24/02	Okuno et al.	257	328	
	7/	6.	6,613,695	09/02/03	Pomarede et al.	438	767	
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EXAMINER INITIAL	DOCUMENT NUMBER	DATE COUNTRY	CLASS	SUBCLASS	TRANSLATION		
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EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
	7. Ikoma et al., Growth of Si/3C-SiC/Si(100) hetrostructures by pulsed supersonic free Jets, Applied Physics Letters, Volume 75, No. 25, Pp. 3977-3979, December 1999

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